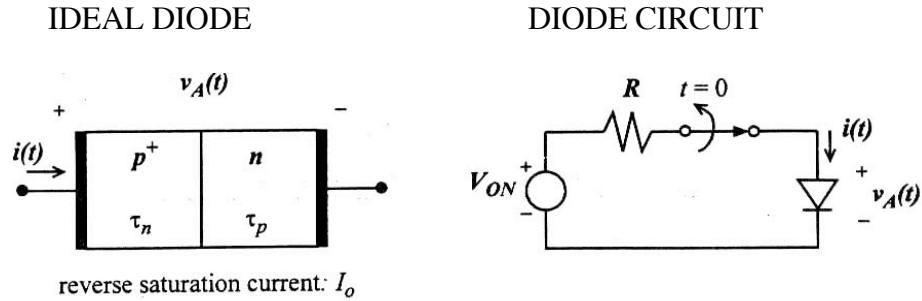


Problem 1 [20 points]

Consider an ideal  $p^+n$  step junction diode in the following circuits:



The switch is closed for all times  $t < 0$ , then opened at time  $t = 0$ .

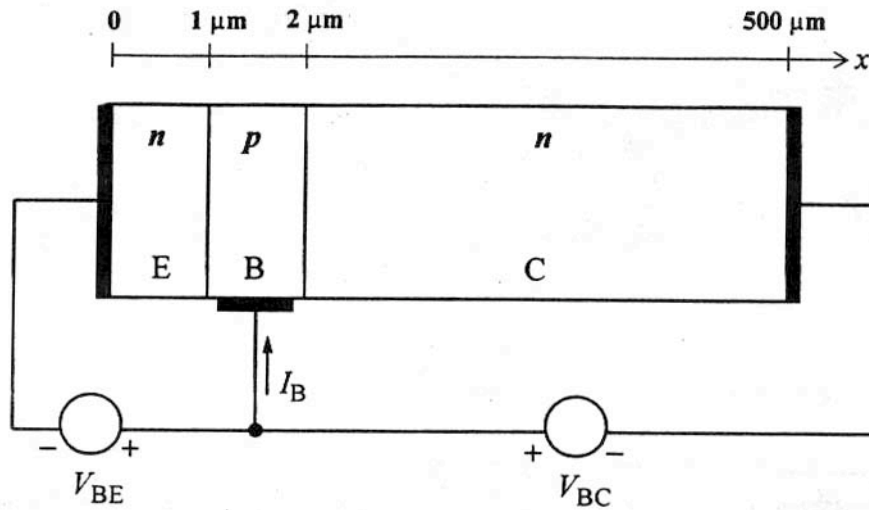
Assume that  $V_{ON} \gg v_A$  so that  $i(t) = V_{ON} / R$  for times  $t < 0$ .

- a) What is the stored hole charge,  $Q_p$ , inside the diode, for times  $t < 0$ ?
- b) Derive an expression for  $Q_p(t)$ , for times  $t > 0$
- c) Derive an expression for  $v_A(t)$ , for times  $t > 0$ .

(Assume that the stored charge decays quasi-statically, i.e. the relationship between  $Q_p$  and  $v_A$  is the same as in steady state.)

Problem 2 [40 points]

Consider the following npn bipolar transistor:



Assume that each region is uniformly doped, and that both the emitter and base are short, while the collector is long.

Doping concentrations:  $N_E = 10^{19} \text{cm}^{-3}$ ,  $N_B = 10^{17} \text{cm}^{-3}$ ,  $N_C = 10^{15} \text{cm}^{-3}$

Minority carrier diffusion constants:  $D_E = 2 \text{cm}^2/\text{s}$ ,  $D_B = 19 \text{cm}^2/\text{s}$ ,  $D_C = 12 \text{cm}^2/\text{s}$

Minority carrier lifetimes:  $\tau_E = \tau_B = \tau_C = 10^{-6} \text{cm}^2$ .

The area of the transistor  $A = 10^{-6} \text{cm}^2$ .

- a) Will this BJT suffer severe base-width modulation under forward active bias operation?

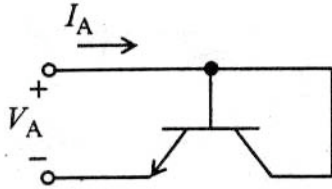
For the remaining sections of this question, consider the case where  $V_{BE} = V_{BC} = 0.6 \text{V}$

- b) Sketch the energy band diagram. (Indicate the Fermi levels in the quasi-neutral regions.)
- c) Sketch the excess minority carrier densities in each region:  $p'_E(x)$ ,  $n'_B(x)$ , and  $p'_C(x)$ . Write the expressions for those. (You may ignore the widths of the depletion regions.)
- d) What is the value of the base current,  $I_B$ , assuming no recombination in the base?

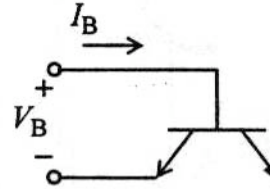
Problem 3 [25 points]

Consider the following two ways to connect an npn BJT as a diode:

**Case A**



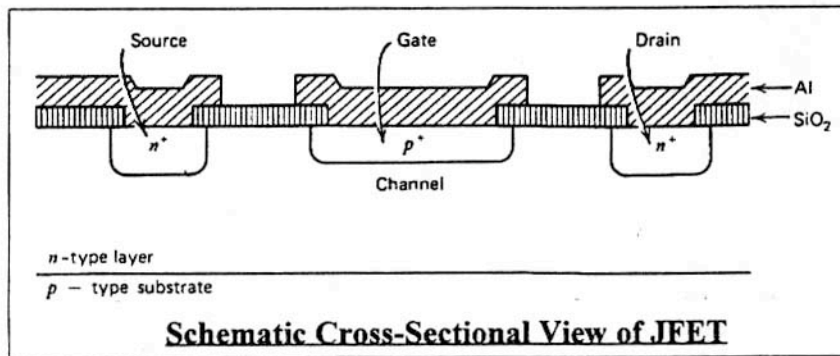
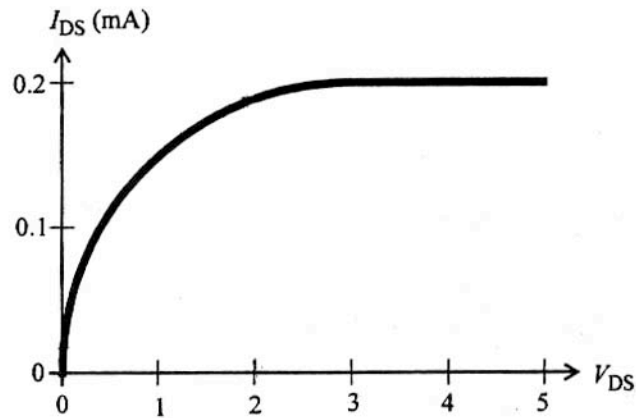
**Case B**



- Derive the I-V relationship for each “diode” from the Ebers-Moll equations.  $I_A$  or  $I_B$  should be expressed only in terms of  $V_A$  or  $V_B$  and the Ebers-Moll parameters ( $\beta_F$ ,  $\beta_R$ ,  $I_{ES}$ ,  $I_{CS}$ ).
- Assume the  $V_A \gg kT/q$  and  $V_B \gg kT/q$ . Sketch the excess minority carrier concentration in the base for each case, indicating the values of  $n'_B$  at the edges of the depletion regions.  
(Assume that the base region of each transistor is short.)  
Note: For case B, you should use the Ebers-Moll equations to find  $[\exp(qV_{BC}/kT) - 1]$  in terms of  $V_B = V_{BE}$ .
- Which connection seems most appropriate for use as a diode? Why?  
(Hints: Compare the switching times for the two cases.)

Problem 4 [15 points]

The following plot is the room-temperature I-V characteristic of an ideal planar Si n-channel JFET with  $W = 10 \mu\text{m}$  and  $L = 5 \mu\text{m}$  and channel doping concentration  $N_d = 10^{16} \text{cm}^{-3}$ .



- a) Estimate the turn-off voltage,  $V_T$ , from the plot above.

If you did not obtain an answer for part (a), use  $V_T = -2\text{V}$  for the remainder of this question.

- b) What is the thickness of the channel,  $t$ ? Assume that the gate region is degenerately doped p-type, and that the width of the depletion region at the channel-substrate junction can be neglected.
- c) Sketch the I-V curve corresponding to  $V_{GS} = -1\text{V}$  on the plot provided. (Indicate values for  $V_{DS}$  at the pinch-off point, and  $I_{DSAT}$ )  
You may use the empirical model:

Sketch the I-V curve on the plot below. [6 pts]

